

ABSTRACT OF THE DISCLOSURE

A fabrication method for an electron source substrate comprises: a measurement step wherein at least one of a substrate, having a plurality of pairs of electrodes on the surface thereof, and measurement means for measuring the position of the substrate in at least one direction of the mutually orthogonal XYZ directions, is scanned relatively in one direction, thereby measuring the substrate position; a control step for controlling the discharge position of droplets containing electroconductive thin-film material onto the substrate from an ink-jet head, based on the measurement results; and a discharge step for discharging the droplets between the pairs of electrodes while relatively scanning at least one of the ink-jet head and substrate in one direction; wherein the scanning direction in the measurement step and the scanning direction in the discharge step are generally parallel; and wherein the measurement step and the discharge step are performed in a single scan.